	L #	Hits	Search Text
11	L11	2503	(plurality near2 (mask or reticle)) with pattern$3
12	L12	102857	(wafer or substrate) same (lithography or exposure or exposing)
13	L13	1522	11 and 12
14	L14	1116	(chang$3 near3 (expos$5 near2 amount))
15	L15	48	13 and 14
16	L16	18	@ad<=19991108 and 15

PK
8/20/04

	L #	Hits	Search Text
1	L1	10	US-5461237-$.DID. OR US-5486896-$.DID. OR US-0553951-$.DID. OR US-5593800-$.DID. OR US-5710620-$.DID. OR US-5801815-$.DID. OR US-5841520-$.DID. OR US-6213607-$.DID. OR US-6337162-$.DID. OR US-6463577-$.DID.
2	L2	1	("5539521").PN.
3	L3	876	((wafer or substrate) near3 (sag$4 or flex$3 or deform$5)) with (measur$5 or detect$4 or sens$4 or determin$5)
4	L4	53501	(mask or reticle) same (lithography or exposure or exposing)
5	L5	172	3 and 4
6	L6	430	((wafer or substrate) near3 (sag$4 or flex$3 or deform$5)) with (correct$4 or compensat$4 or adjust$5)
7	L7	52	5 and 6
8	L8	31	@ad<=19991108 and 7
9	L9	1	628363.ap. and zero
10	L10	1	628363.ap. and chuck$3